

# 面向电路拓扑的GaN器件导通电阻 测试方法与标准建议

仅限PMIC会员单位内部使用，不得外传

吴新科 教授

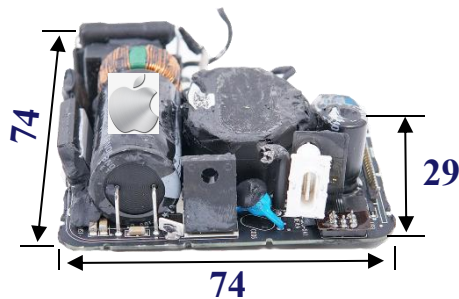
**ZJU-PMIC**

浙江大学电力电子技术研究所

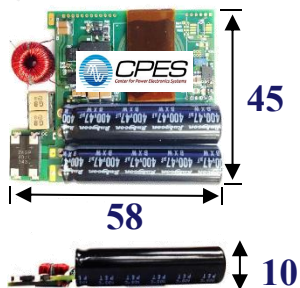


# Advantages of GaN Power Converters: High Efficiency High Power Density

## ■ 65W power adapter

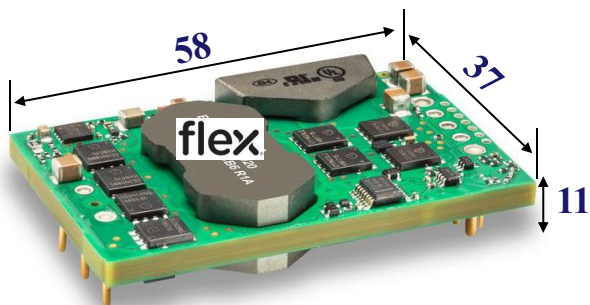


**Si** 120kHz, 7W/in<sup>3</sup> [1]

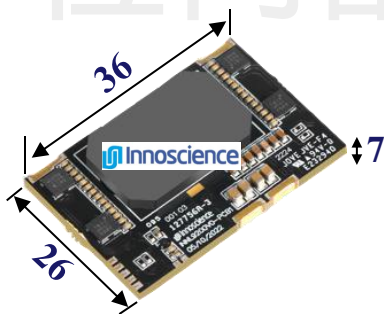


**GaN** 1MHz, 41W/in<sup>3</sup> [2]

## ■ On board DC/DC module

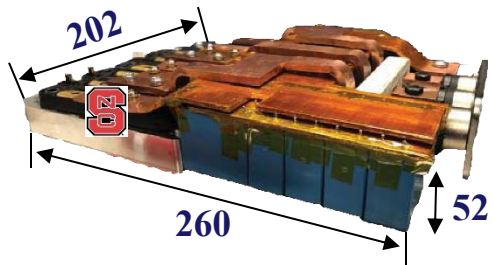


**Si** 180kHz, 412W/in<sup>3</sup> [3]

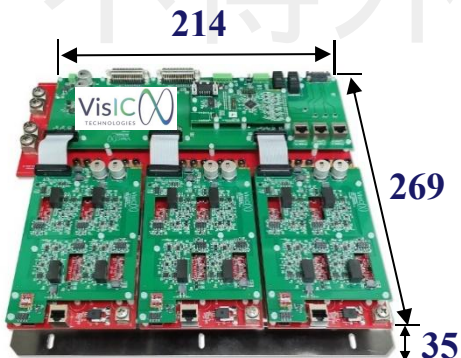


**GaN** 1MHz, 1500 W/in<sup>3</sup> [4]

## ■ Inverters



**SiC** 40kHz, 557 W/in<sup>3</sup> [5]



**GaN** 100kHz, 820 W/in<sup>3</sup> [6]

[1] <https://post.smzdm.com/p/a25g6vz2/>

[2] X. Huang "Design consideration of MHz active clamp flyback converter with GaN devices for low power adapter application,"

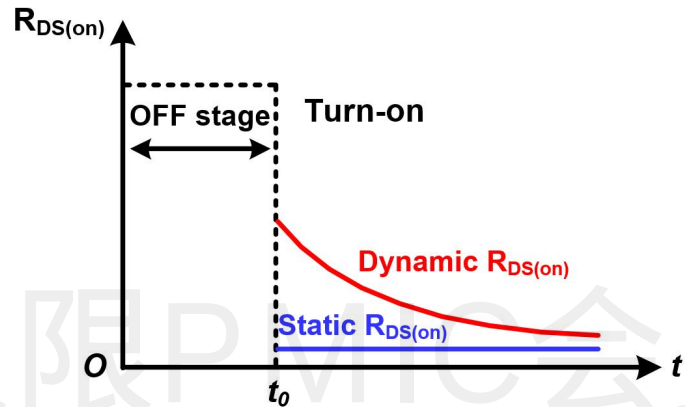
[3] Flex, BMR458 series

[4] <https://laoyaoba.com/n/826044>

[5] C. Zhang "A SiC-Based 100 kW High-Power-Density (34 kW/L) Electric Vehicle Traction Inverter,"

[6] VisiC, 800V 100kW 3-Phase GaN Inverter

## ■ Dynamic $R_{DS(on)}$ Degradation



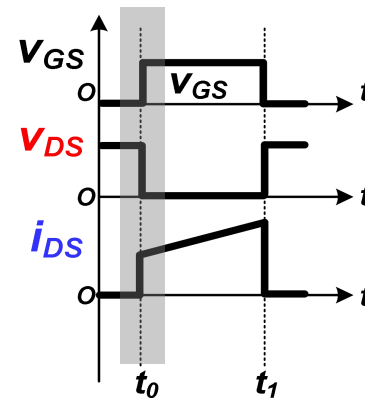
- Conduction loss Increase
- Difficult to estimate real loss

## ■ Facts of Dynamic $R_{DS(on)}$

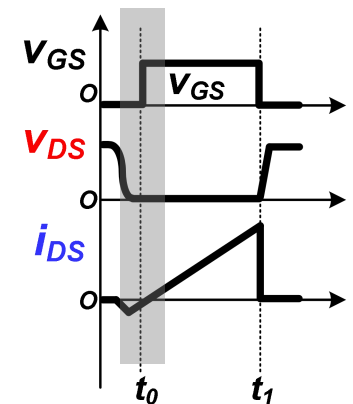
- $dR_{DS(on)} \propto$
- OFF-state drain bias voltage
  - Load current
  - Junction temperature
  - .....

## ■ Relationship between Dynamic $R_{DS(on)}$ and switching conditions

### □ Hard Sw.

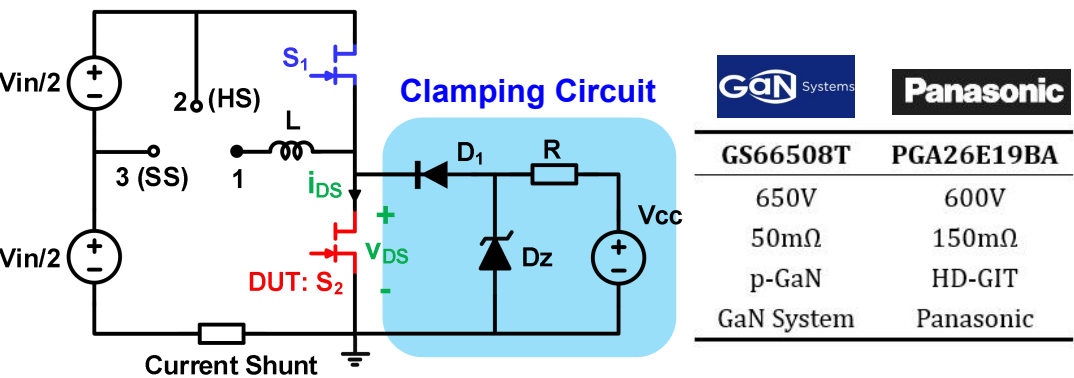


### □ Soft Sw.

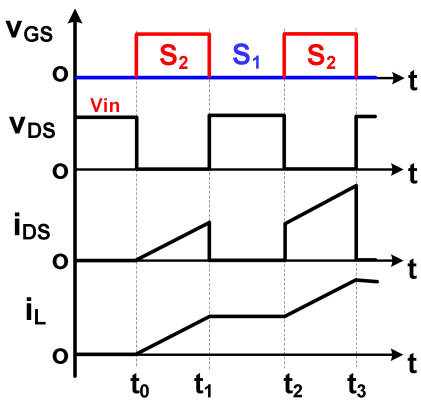


Dynamic  $R_{DS(on)}$  can only be obtained by measurement

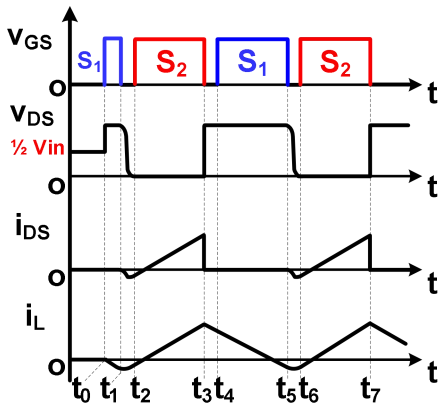
# GaN Device's $R_{DS(on)}$ Behaves Differently under Hard- and Soft- Switching Conditions [7]



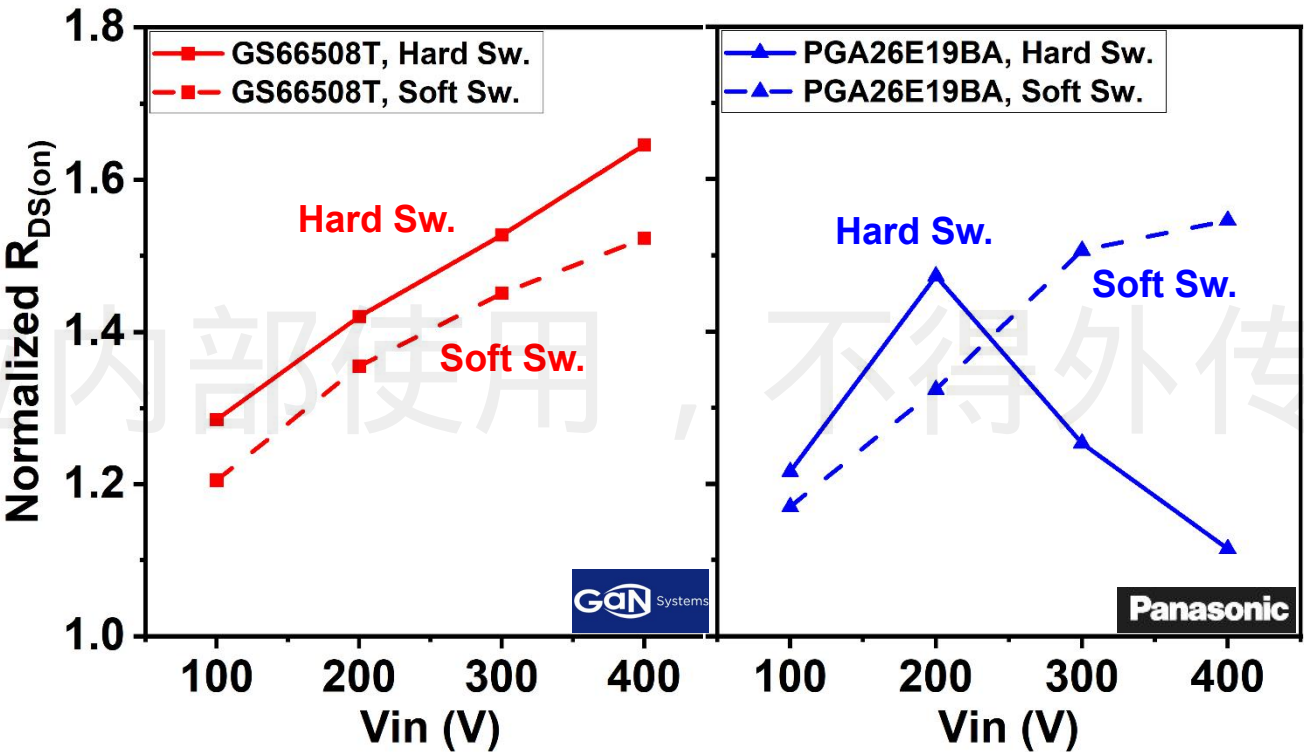
## Hard Sw. Test



## Soft Sw. Test



## Double Pulse Test (DPT) @2μs on-time

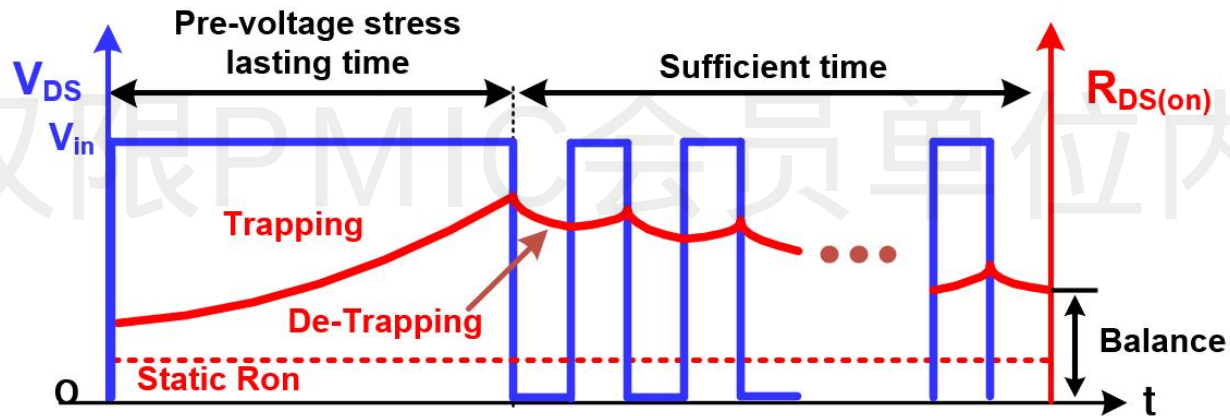


$R_{DS(on)}$  change differs under HS and SS.

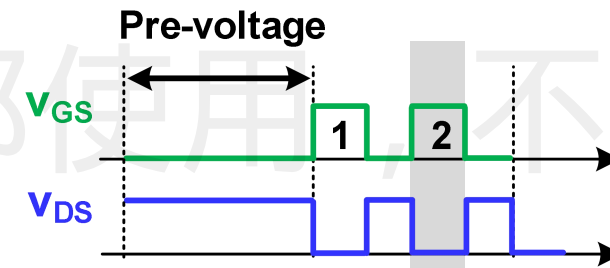
[7] R. Li, X. Wu, S. Yang, and K. Sheng, "Dynamic on-State Resistance Test and Evaluation of GaN Power Devices Under Hard- and Soft-Switching Conditions by Double and Multiple Pulses," IEEE Trans. Power Electron., vol. 34, no. 2, pp. 1044–1053, Feb. 2019



## ■ $V_{DS}$ bias effect in continuous pulse [10]



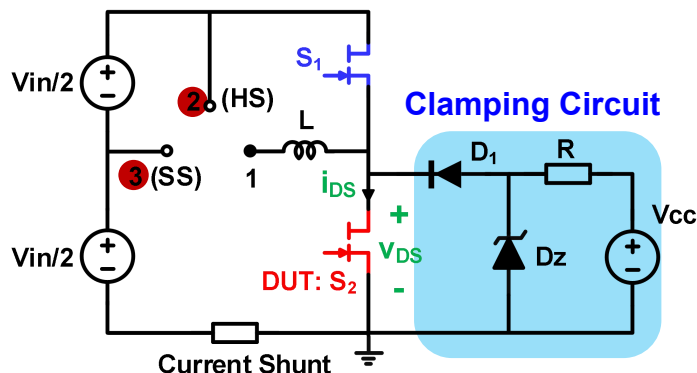
## ■ DPT for dynamic $R_{DS(on)}$



□ pre-voltage can't be ignored.

[10] K. Li, P. L. Evans, C. M. Johnson, A. Videt, and N. Idir, "A GaN-HEMT Compact Model Including Dynamic  $R_{DS(on)}$  Effect for Power Electronics Converters,".

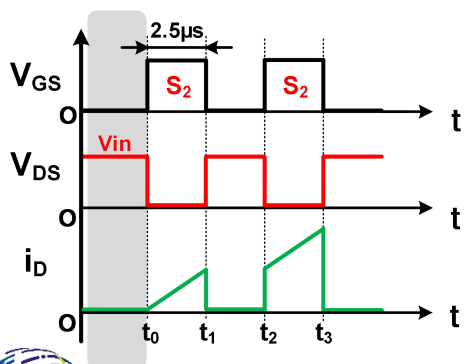
# Different Influence of Pre-voltage Stress for Different GaN Devices under DPT



Same operation under Hard Sw.

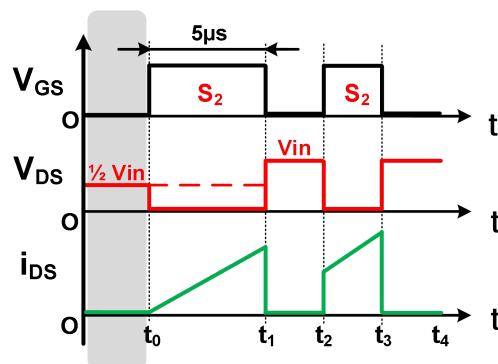
■ 1 to 2

Pre-voltage stress =  $V_{in}$

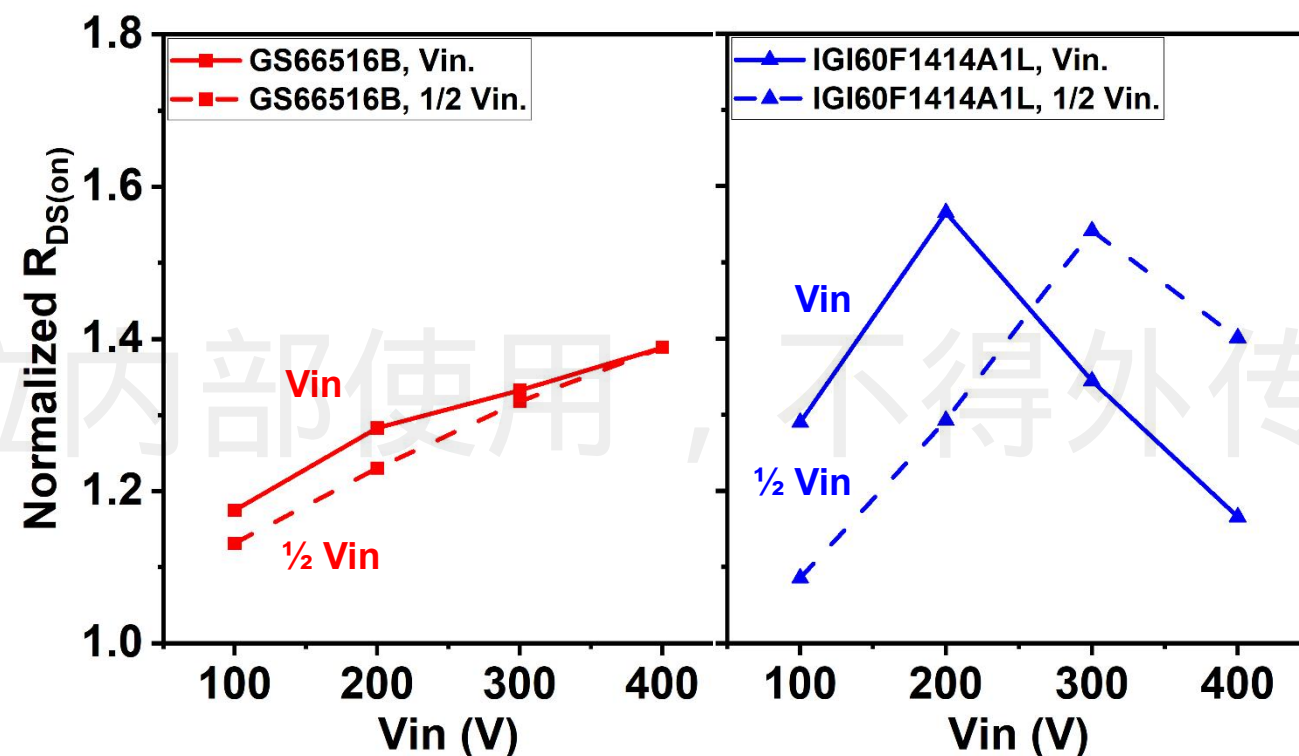


■ 1 to 3

Pre-voltage stress =  $\frac{1}{2} V_{in}$



➤ DPT Results @2.5μs on-time

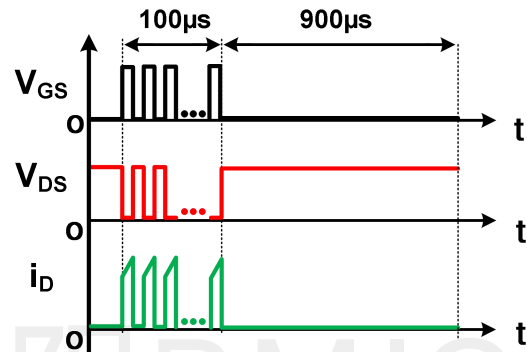


❑ Different devices have different deterioration caused by pre-stress

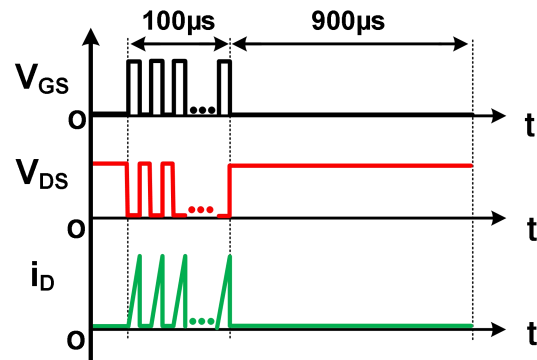


# 100 $\mu$ s Multi-Pulses Test (MPT) has Serious Self-heating

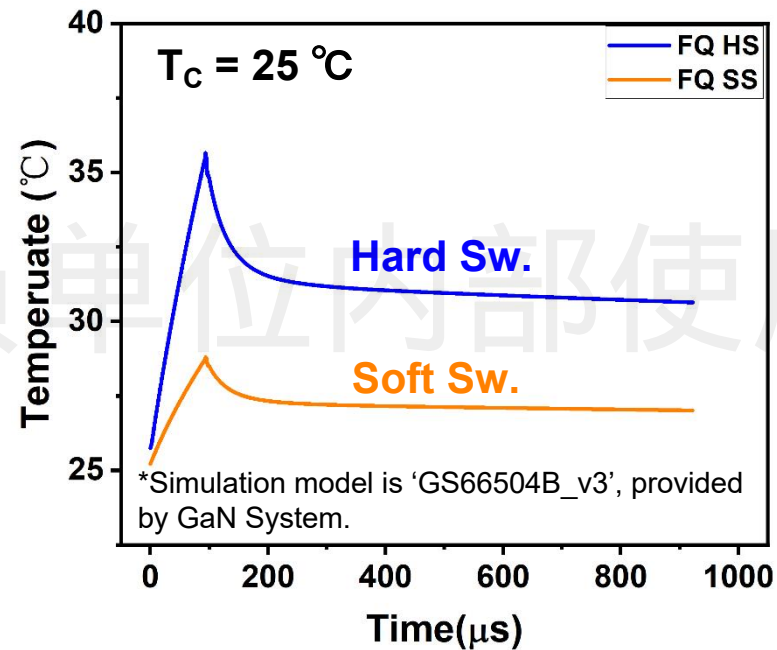
## ➤ 200kHz Hard Sw.



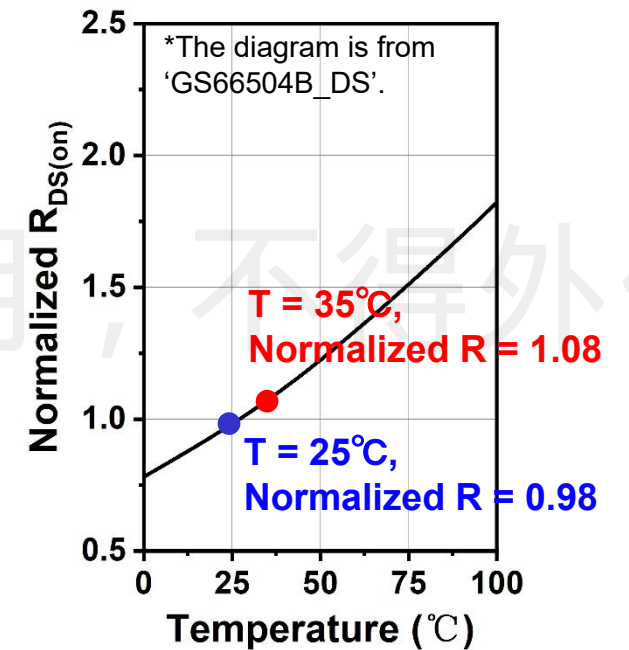
## ➤ 200kHz Soft Sw.



## ■ Thermal Simulation in PLECS



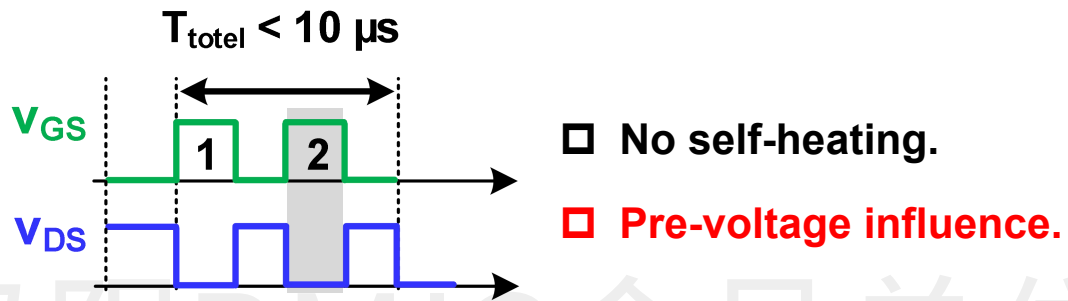
## ■ $R_{DS(on)}$ Temp. Dependence



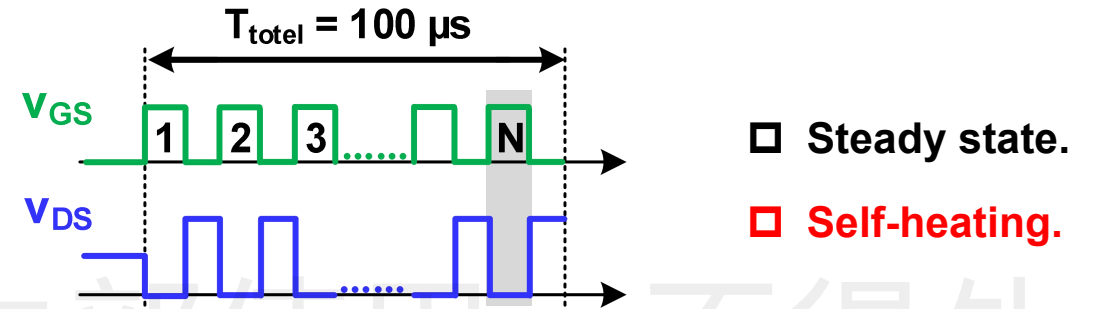
➤ MPT is still unsuitable for dynamic  $R_{DS(on)}$  measuring.

# Multi-group Double Pulse Test (MGDPT) is Selected

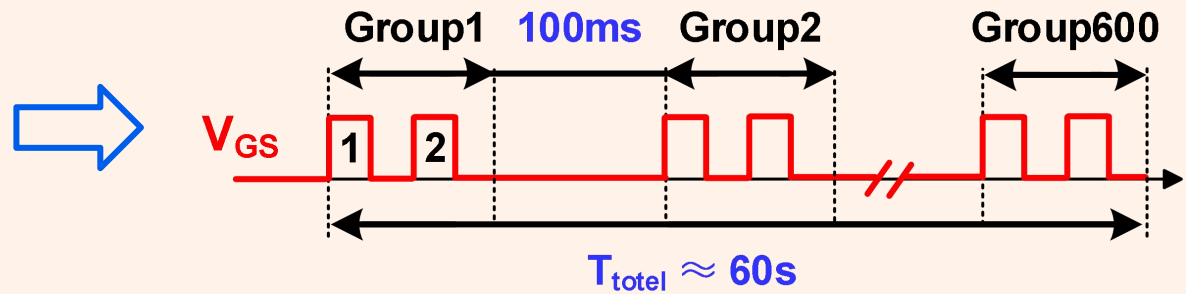
## ➤ Double Pulse Test (DPT)



## ➤ Multi-pulse Test (MPT)

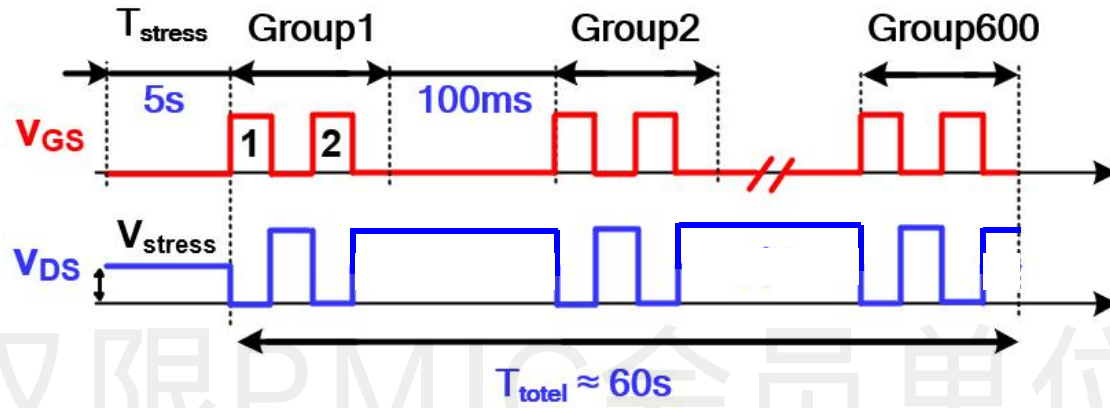


## ➤ Multi-group double pulse test (MGDPT) [11]



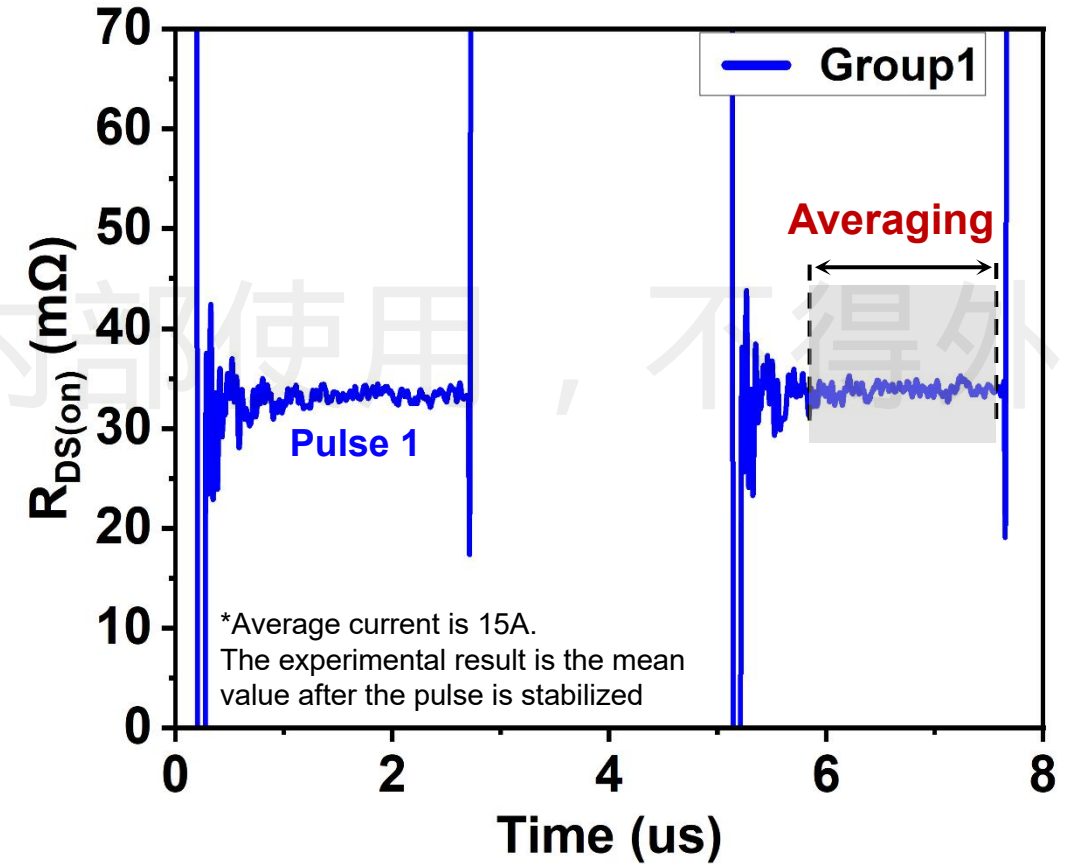
- ❑ Sufficient off-state pulse width for heat dissipation.
- ❑ Sufficient total time for reaching the steady state.

# Multi-group DPT's Experimental Conditions and Data Processing Methods

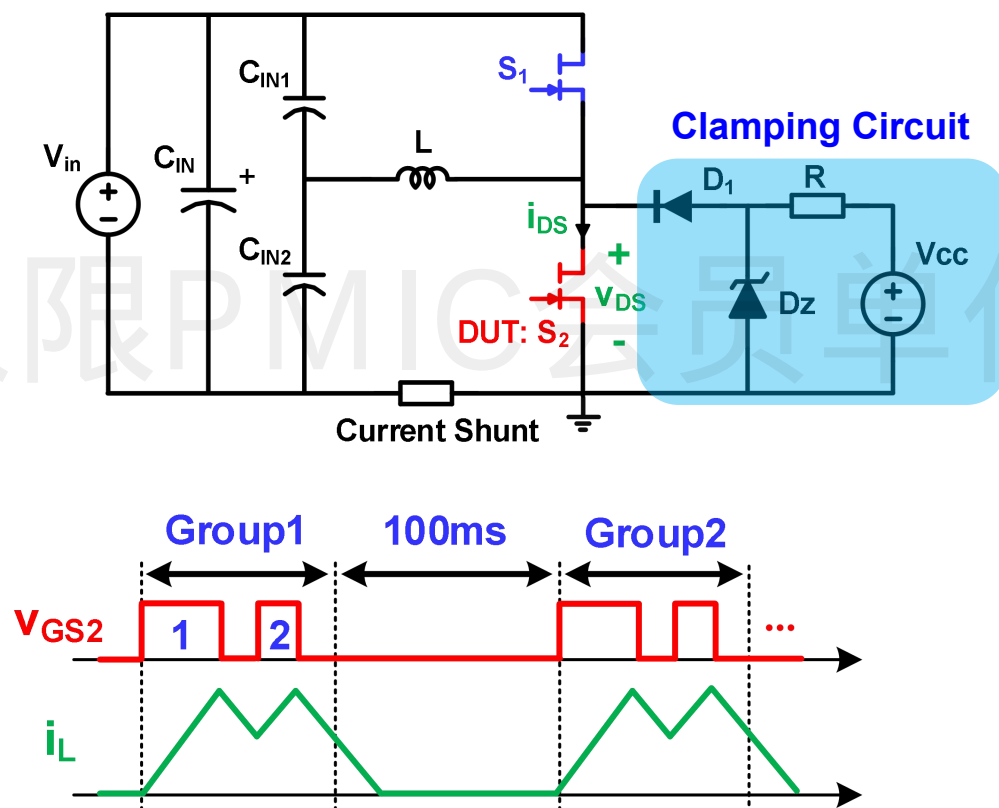


- Pre- $T_{stress}$  = 5 s
- Pre- $V_{stress}$  =  $\frac{1}{2} V_{BUS}$
- On-time = 2.5  $\mu$ s

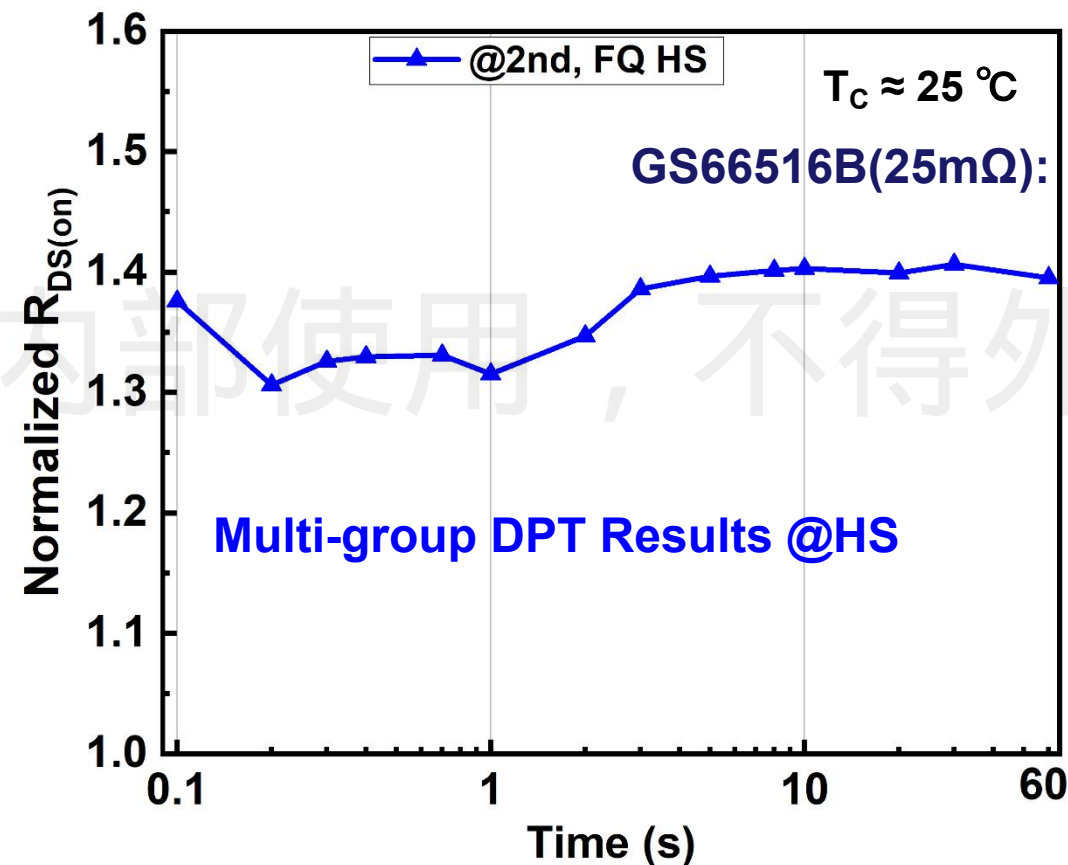
## ➤ Multi-group DPT @400V, Hard Sw.



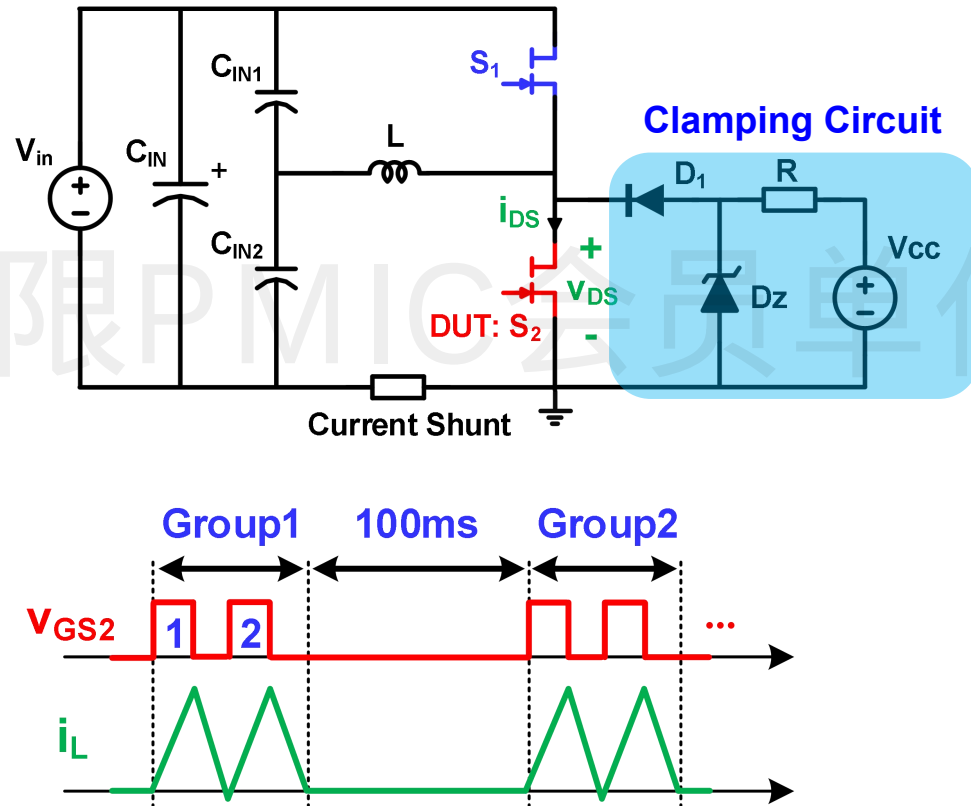
## ■ Hard Switching Bench Circuit



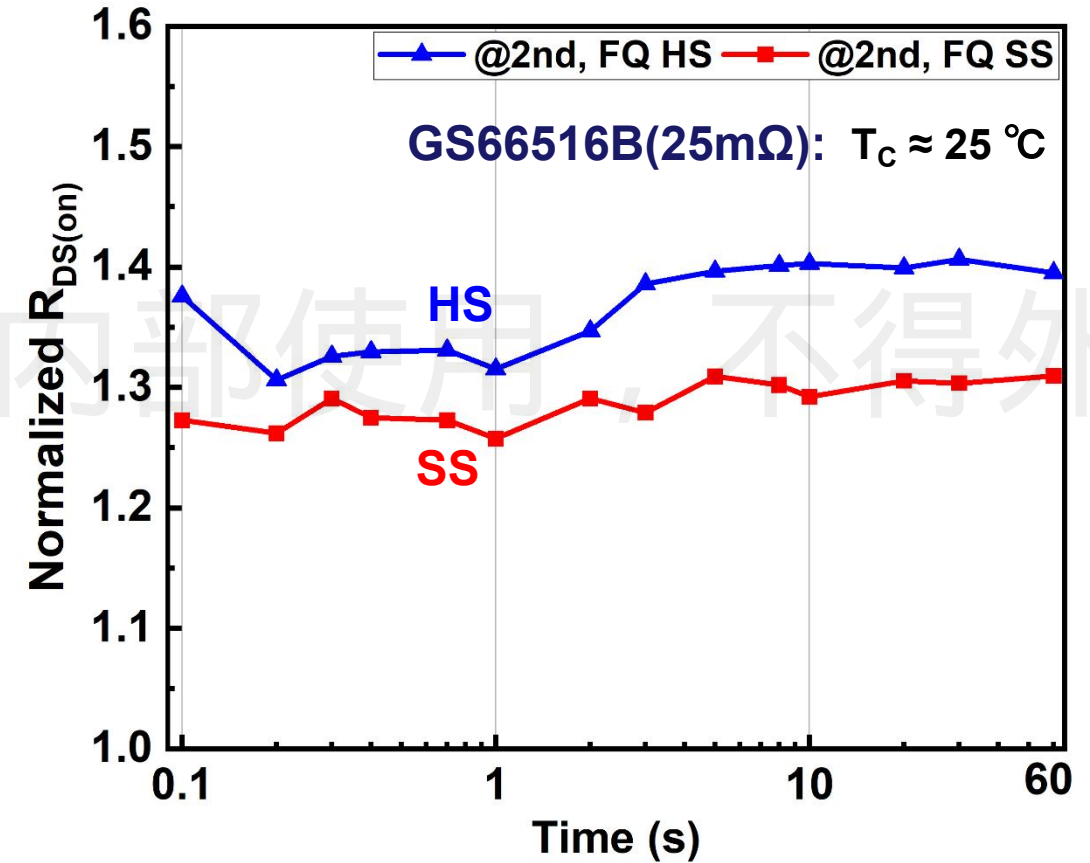
➤ @400V, 2.5 $\mu$ s on-time



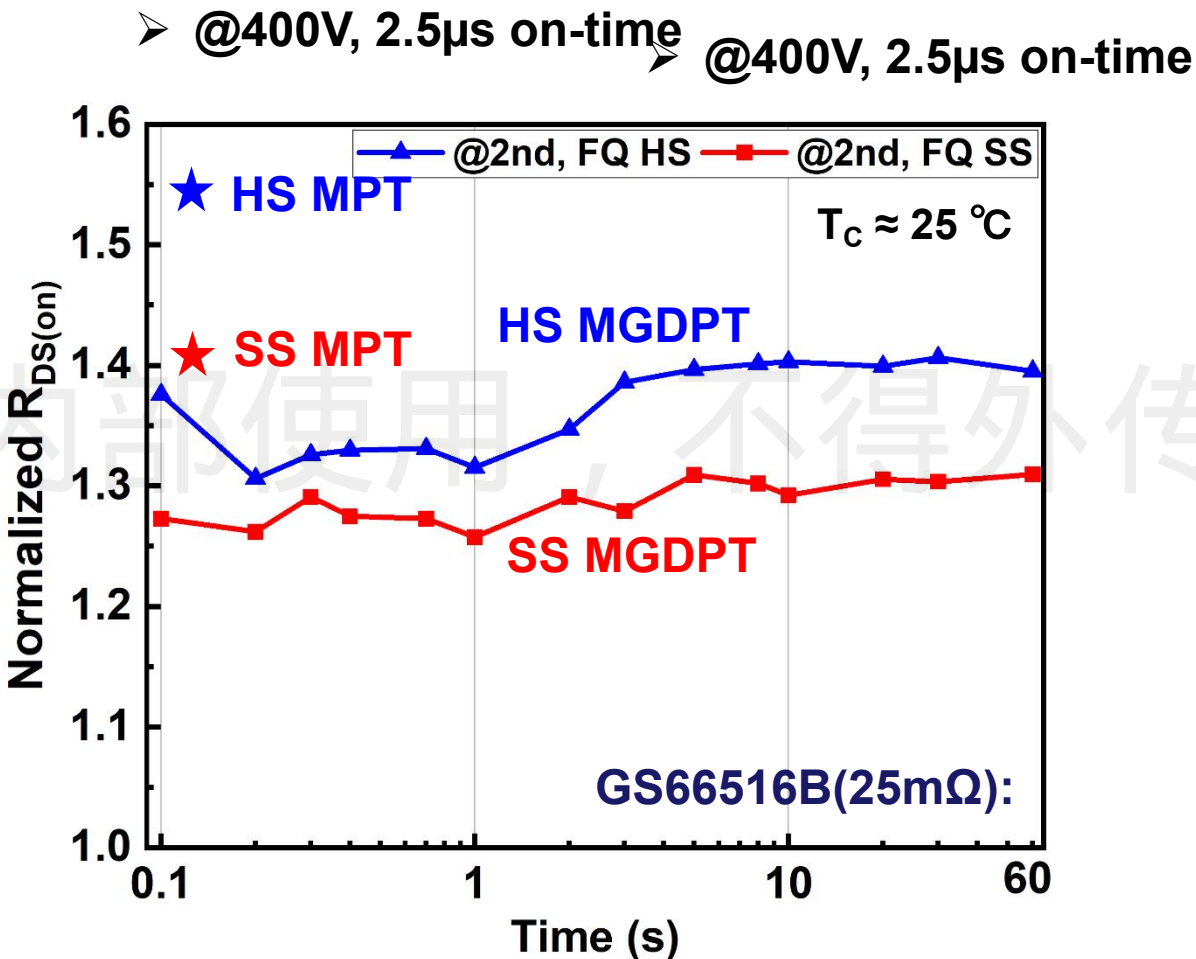
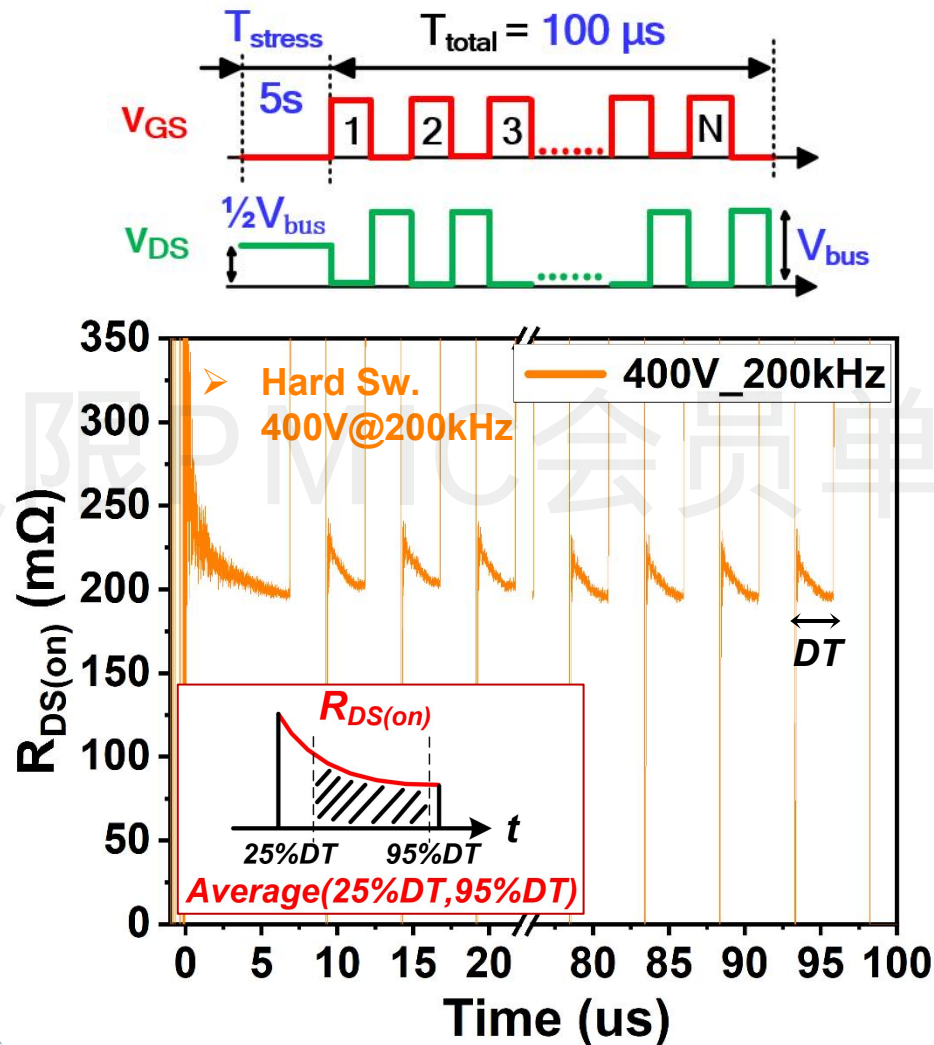
## ■ Soft Switching control method



## ➤ @400V, 2.5μs on-time

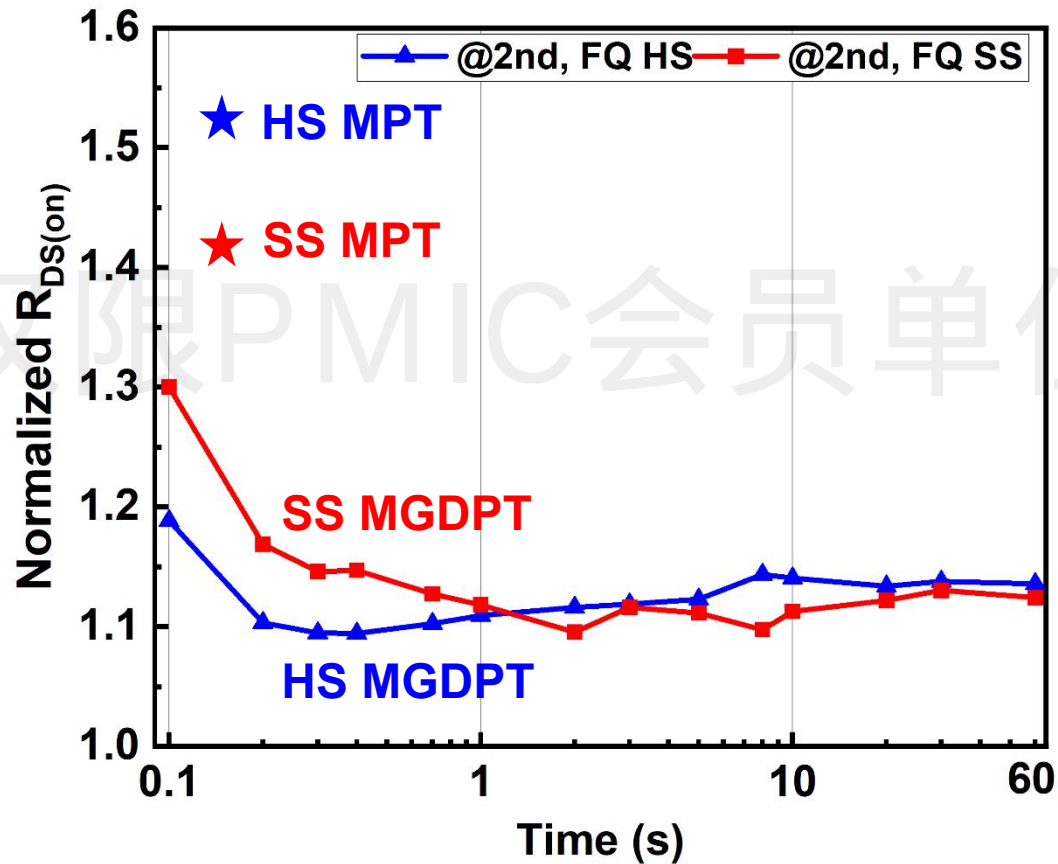


# Comparison between MPT and MGDPT

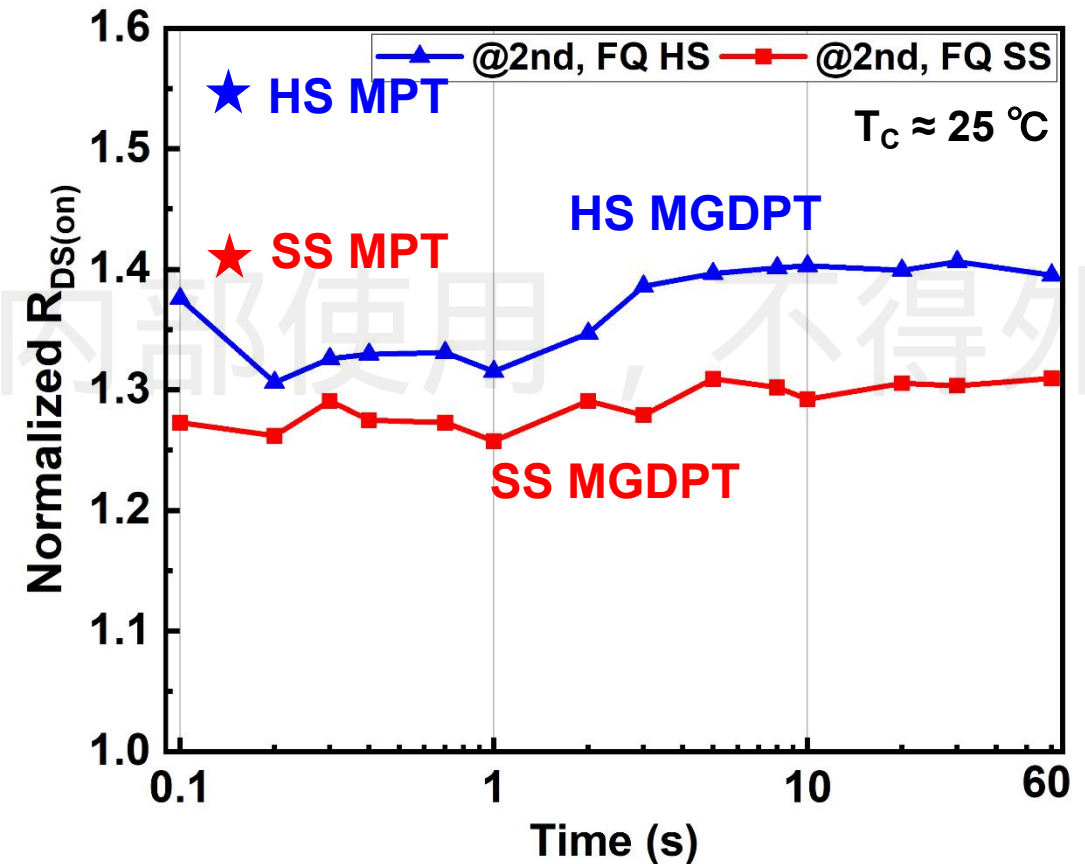


# Test Results Comparison between Different GaN Devices under MGDPT and MPT (FQ@400V)

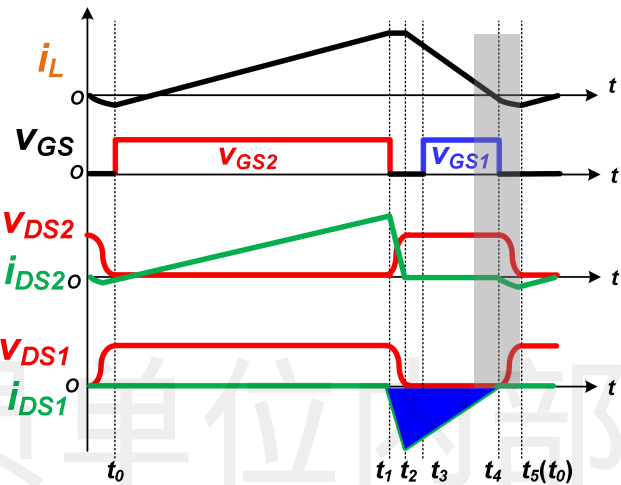
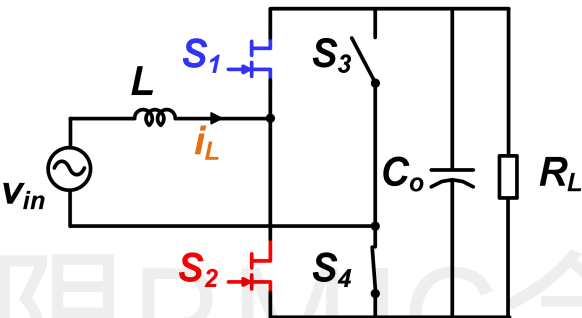
➤ IGI60F1414A1L (HD-GIT) 140mΩ



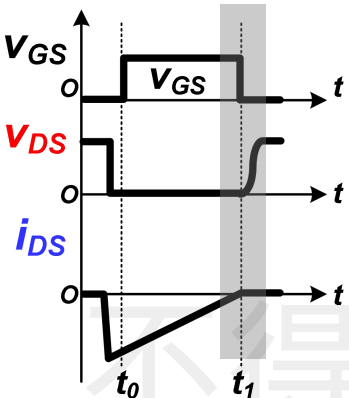
➤ GS66156B (p-GaN) 25mΩ



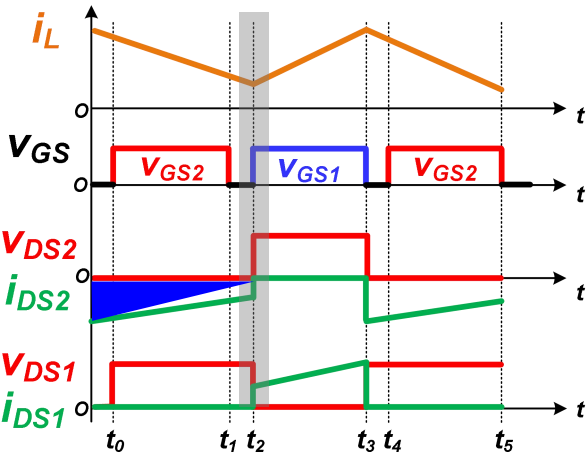
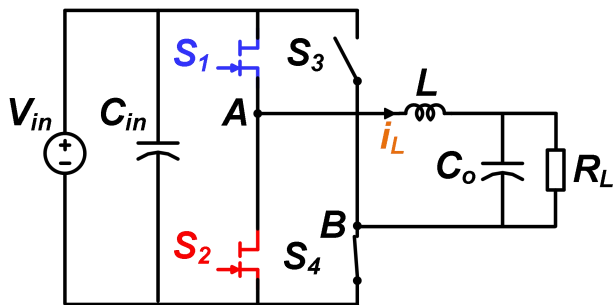
■ Totem Pole PFC



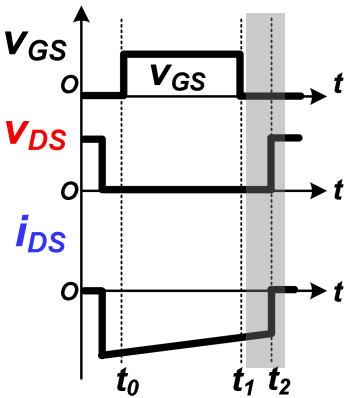
□ Third Quadrant Soft Sw.



■ Inverter

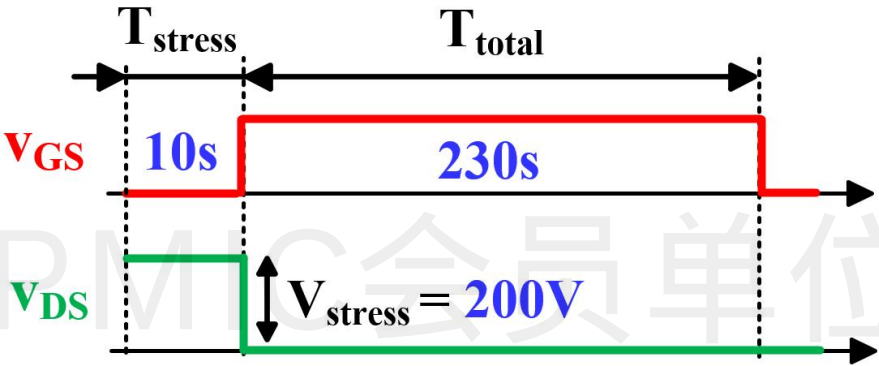


□ Third Quadrant Hard Sw.

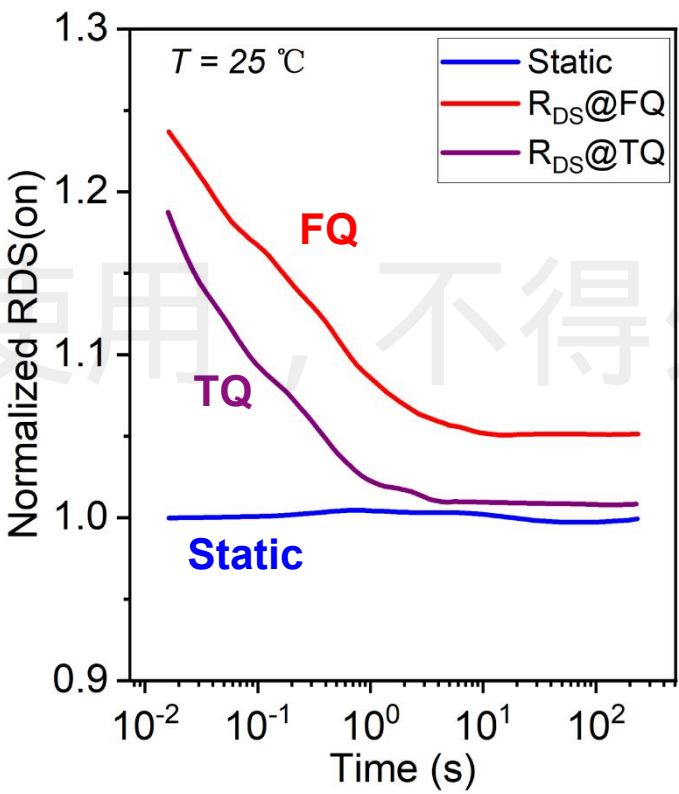


# Third Quadrant $R_{DS(on)}$ Behavior of GaN Devices is Different with First Quadrant [12]

■  $T_{\text{stress}} = 10 \text{ s}$ ,  $V_{\text{stress}} = 200 \text{ V}$ ,  $T_{\text{total}} = 230 \text{ s}$



Conventional p-GaN gate HEMT[12]



**Conclusion:**

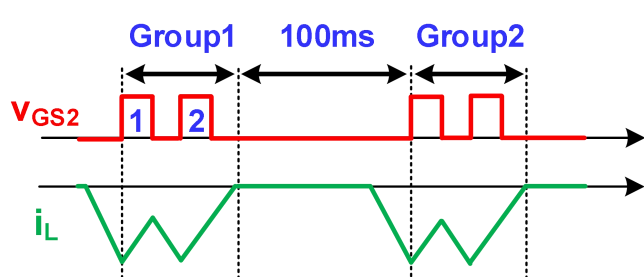
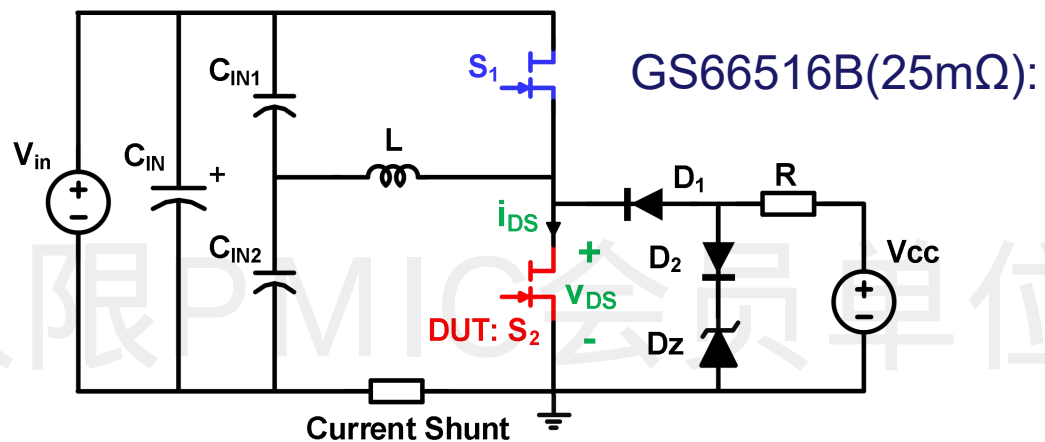
❑ In third quadrant, dynamic  $R_{DS(on)}$  degradation is slightly.

**Areas for improvement:**

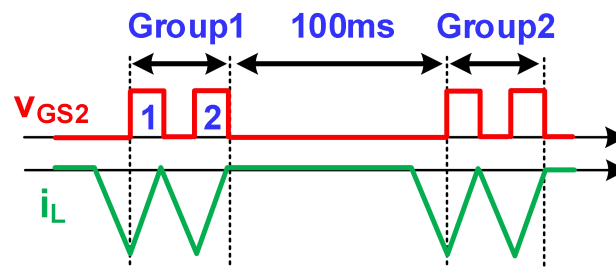
❑ Considering higher voltage stress、Applying multi-group DPT

[12] D. Cingu et al., “Reliability of p-GaN Gate HEMTs in Reverse Conduction,” IEEE Trans. Electron Devices, vol. 68, no. 2, pp. 645–652, Feb. 2021

## Third Quadrant Test Bench

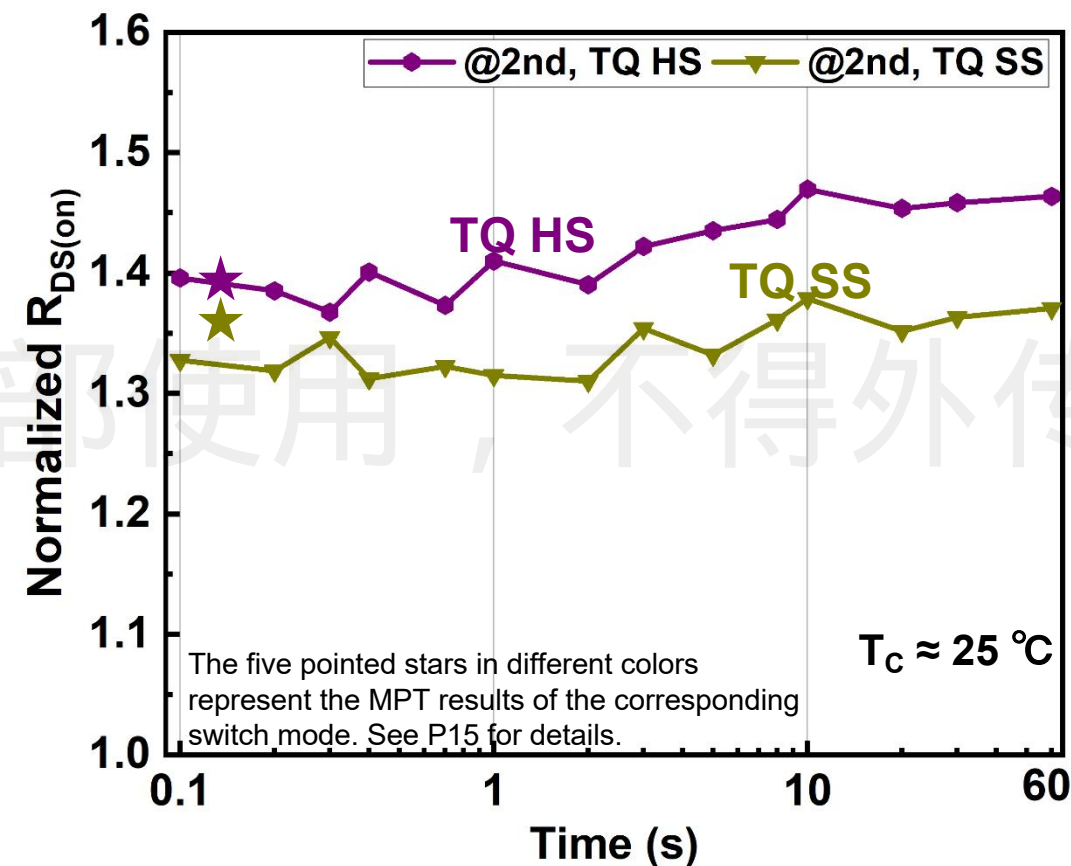


HS test waveforms



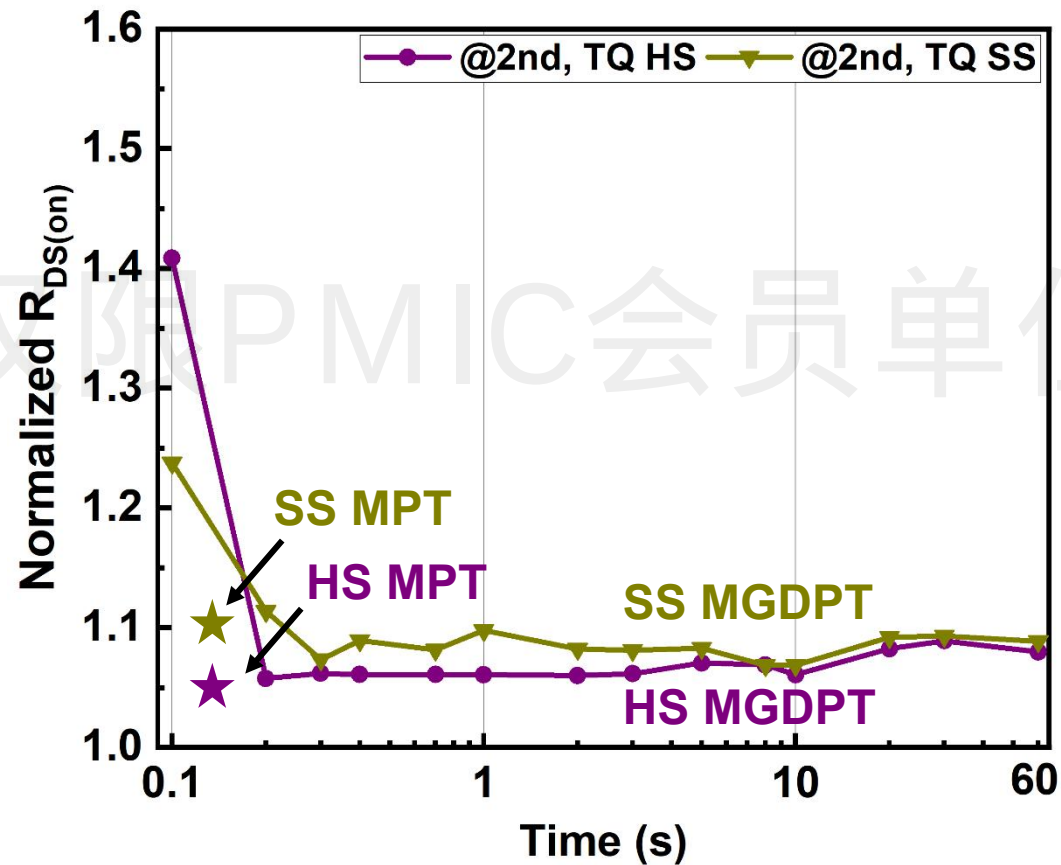
SS test waveforms

➤ @400V, 2.5μs on-time

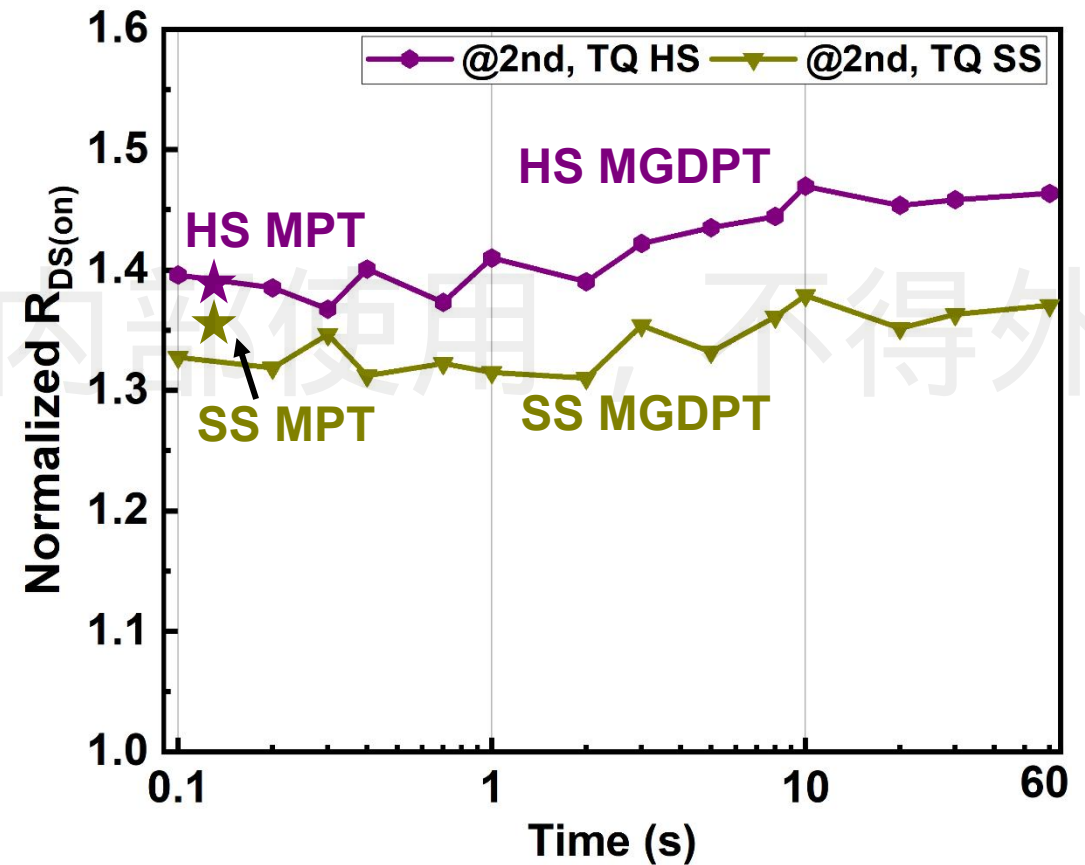


# Test Results Comparison between Different GaN Devices under MGDPT and MPT (TQ@400V)

➤ IGI60F1414A1L (HD-GIT) 140mΩ



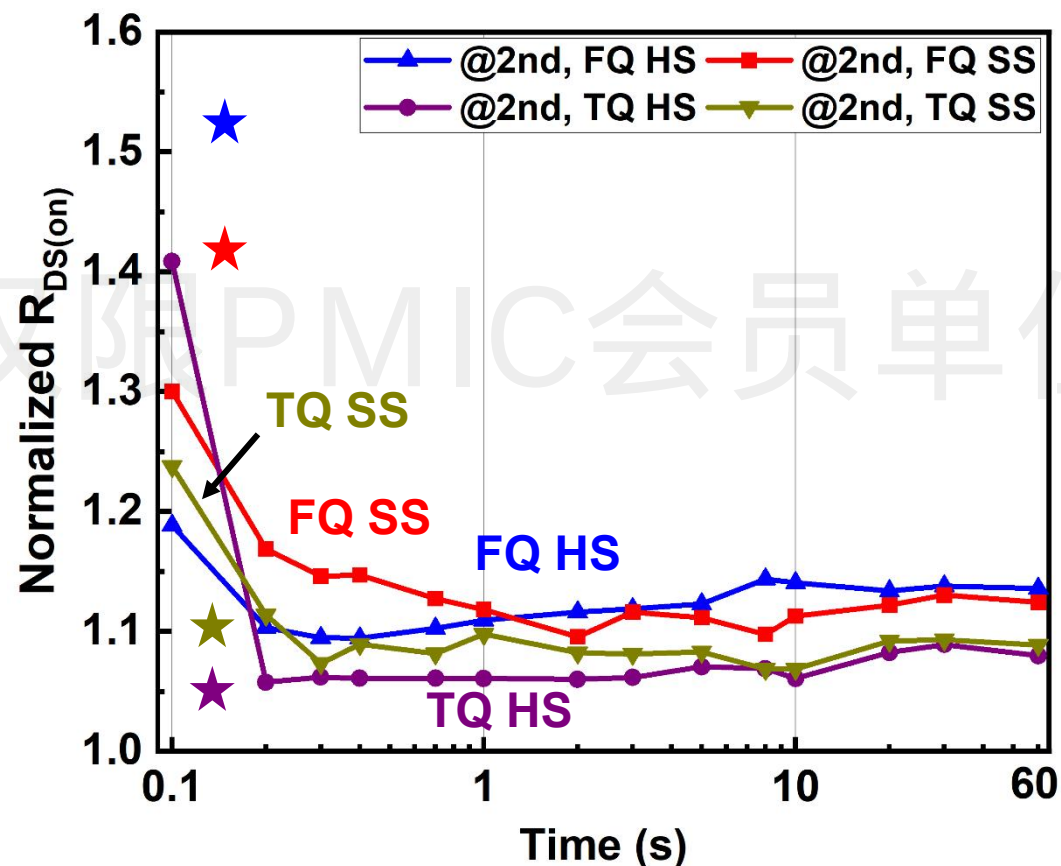
➤ GS66156B (p-GaN) 25mΩ



# Summary of Multi-group DPT Results under 1<sup>st</sup> & 3<sup>rd</sup> Quadrant @400V

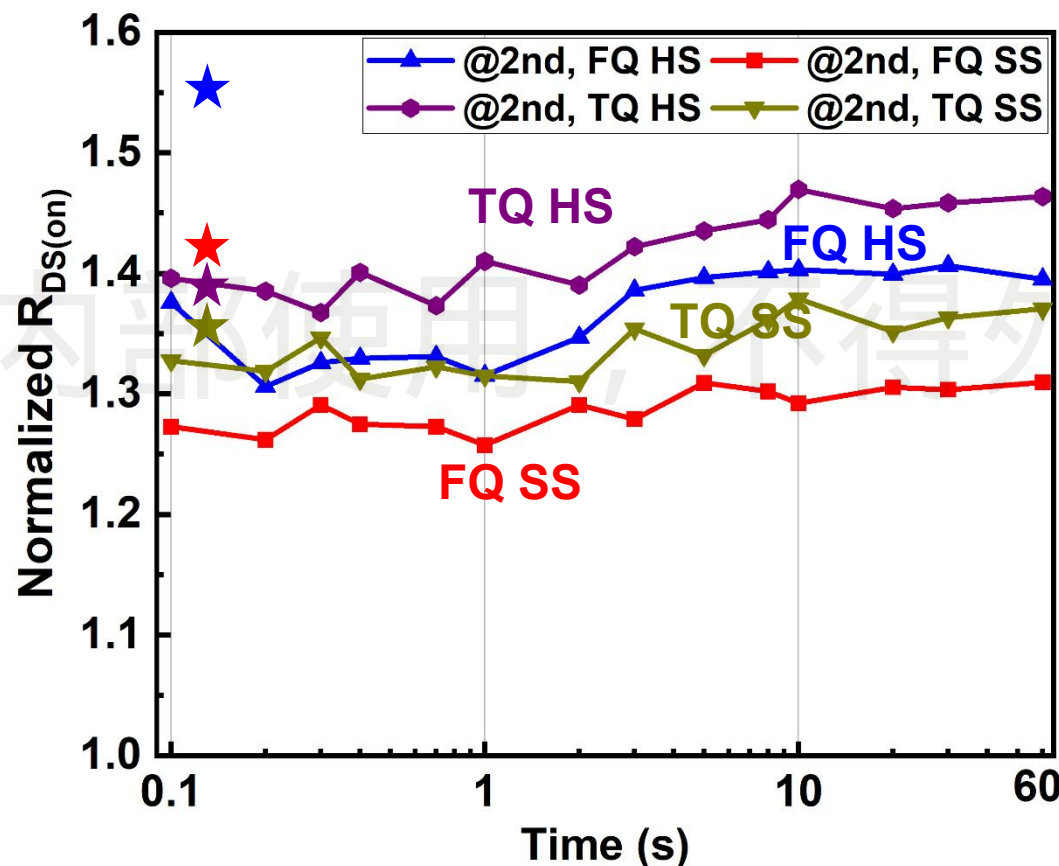
## ➤ IGI60F1414A1L (HD-GIT)

140mΩ



## ➤ GS66156B (p-GaN)

25mΩ



- 1. Test Bench for dynamic resistance of GaN device should consider the effect of numerous parameters, such as different detrap time of different devices structures, pre-stress, pulses, junction temp.,etc.**
- 2. 3<sup>rd</sup> quadrant conducting of GaN is different to 1<sup>st</sup> quadrant , the dynamic resistance evaluation of GaN should consider it.**

仅限PMIC会员单位内部使用，不得外传

装置与系统公司 (22)

元器件公司 (10)





高校主导、行业共建的电源管理技术生态链



| 矽力杰半导体 |
|--------|
| 杰华特半导体 |
| 铭普光磁   |
| 芯朋微    |
| 纳微半导体  |
| 英诺赛科   |
| 横店东磁   |
| 希磁科技   |
| 晶丰明源   |
| 英飞凌    |

| 深圳英飞源技术    | 杭州英飞特新能源 |
|------------|----------|
| 杰瑞电子(716所) | 奥海科技     |
| 长城电源       | 麦田能源     |
| 杭州富特科技     | 酷科电子(紫米) |
| 铂科电子       | 茂硕电源     |
| 皓文电子       | 深圳雷能     |
| 麦格米特       | 欣锐科技     |
| 航芯源        | 爱科赛博     |

| OPPO技术 |
|--------|
| 台达电子   |
| VIVO技术 |
| 中兴通讯   |
| 蔚斯博系统  |
| 小米科技   |

- 合作生态
- 模式探索
- 共性基础
- 未来技术

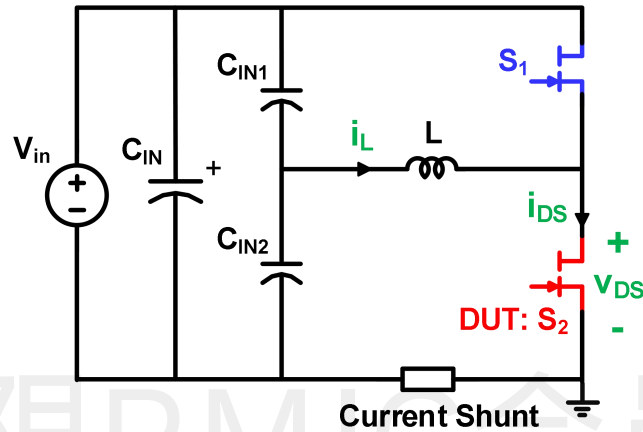
Https: PMIC.ZJU.EDU.CN



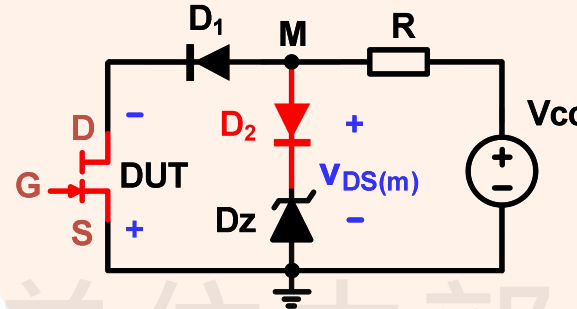
***Thank you  
for your time***

仅限PMIC会员单位内部使用，不得外传





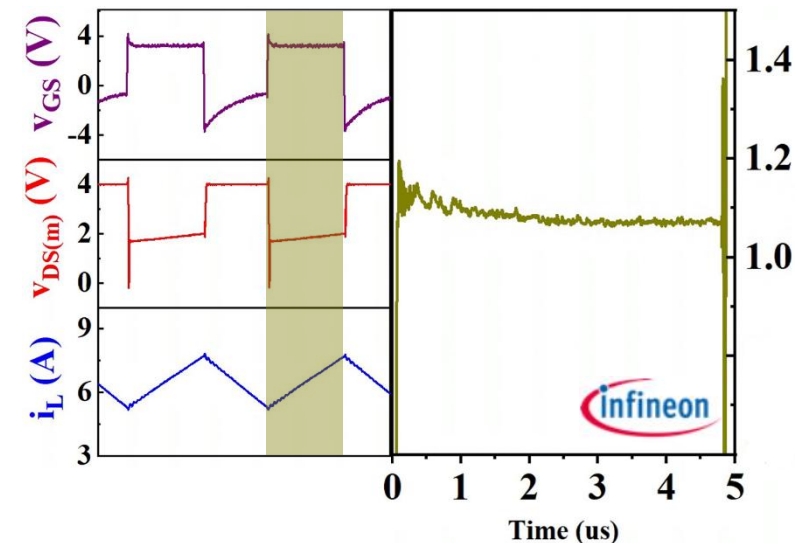
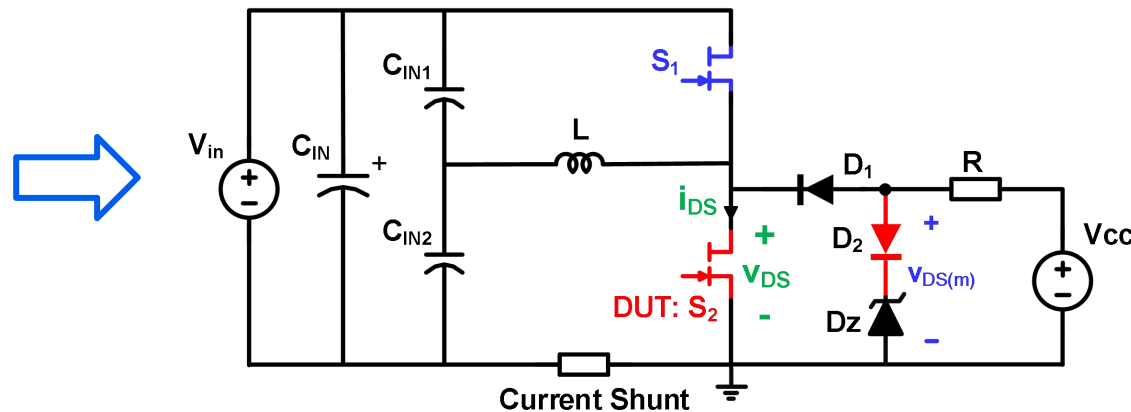
## Improved Clamping Circuit



- Introduce D2 to block Dz's current
- Can be used in first and third quadrants.

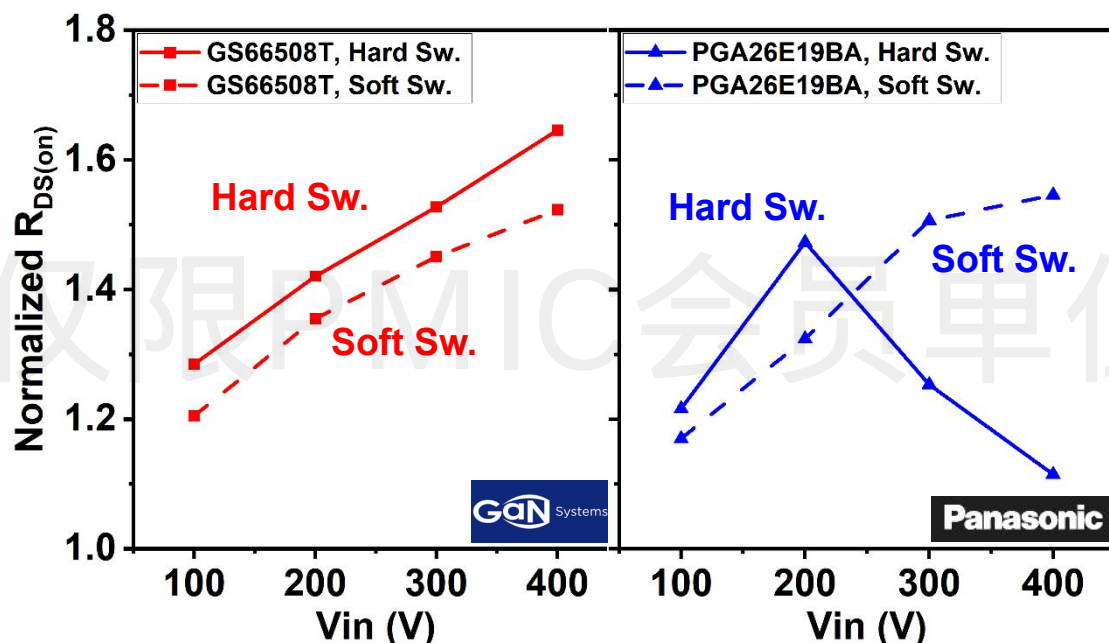
$$\text{Dynamic } R_{\text{DS(on)}} = (V_{\text{DS(m)}} - V_{\text{D1}}) / i_{\text{DS}}$$

➤ IGI60F1414A1L @100V

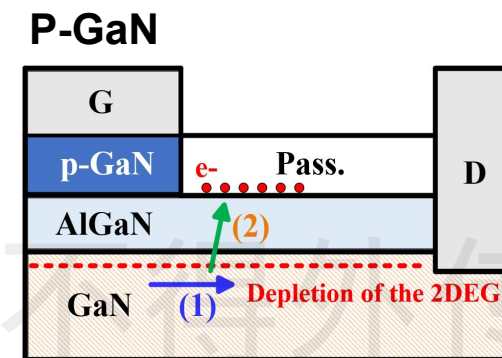
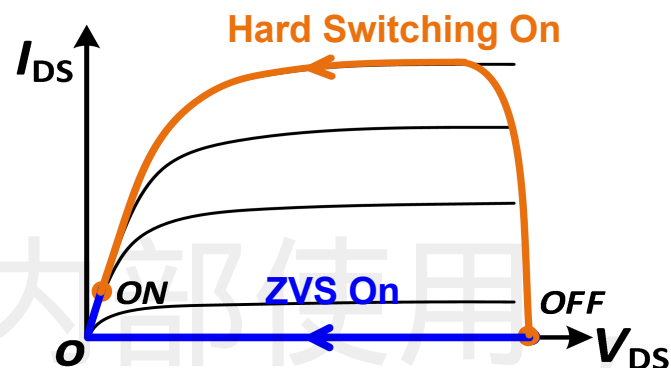


# Hot Electrons Effect makes $R_{DS(on)}$ Higher under Hard Switching Conditions

## Double Pulse Test (DPT) @2 $\mu$ s on-time



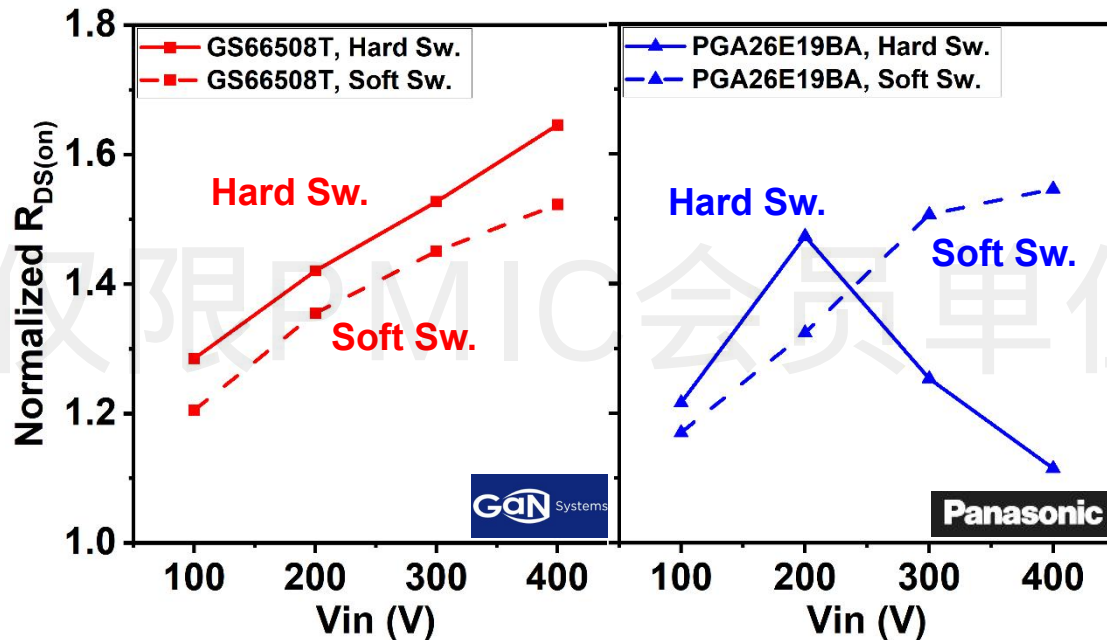
## Hot electrons effect (沟道热电子效应)



- ❑ Electric Field makes electrons “hot”.
- ❑ Lead  $R_{DS(on)}$  increase.
- ❑  $R_{DS(on)}$ : Soft Sw. < Hard Sw.

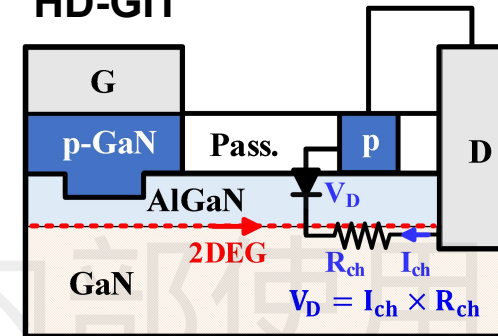
➤ Hot electrons effect dominates in p-GaN type device.

## Double Pulse Test (DPT) @2 $\mu$ s on-time

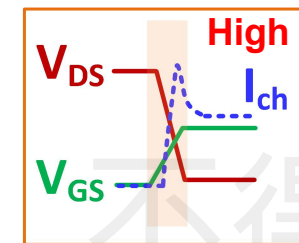


## Hole injection effect (空穴注入效应)

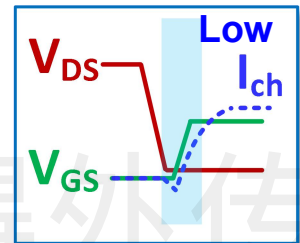
### HD-GIT



### Hard Sw.

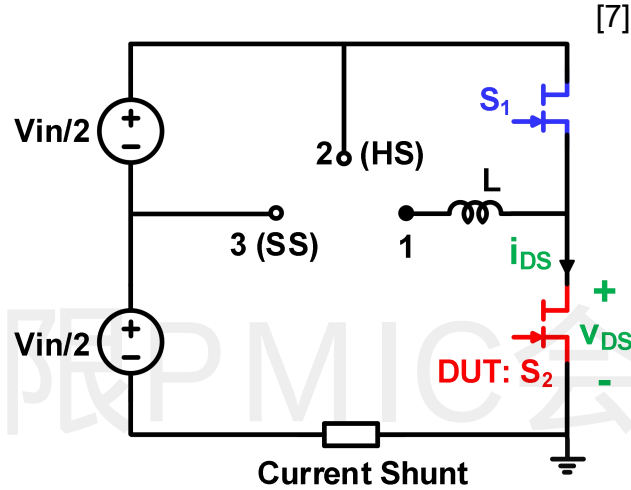


### Soft Sw.



- High  $I_{ch}$  makes PN junction turn on.
- Dynamic  $R_{on}$  is suppressed
- $R_{DS(on)}$ : Soft Sw. > Hard Sw.

➤ Hole Injection Effect plays a significant role in HD-GIT @ $V_{in} = 400V$

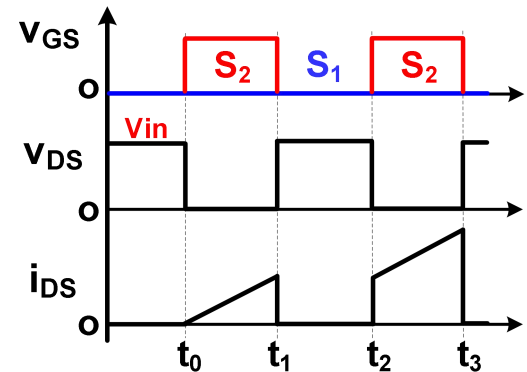
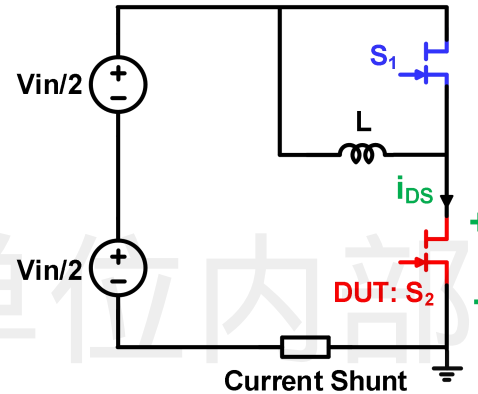


□ Different switching mode

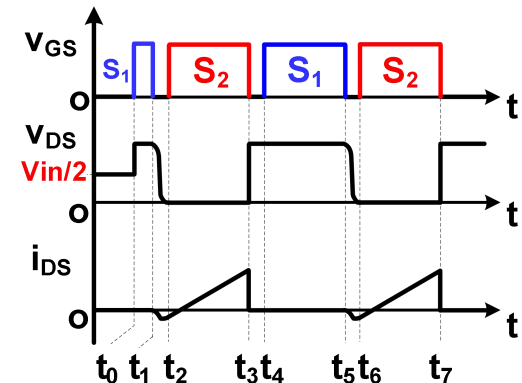
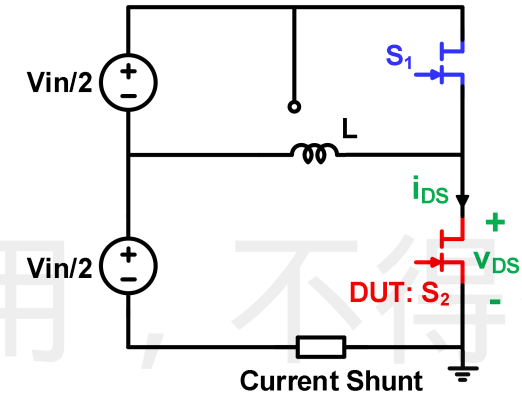
□ Different pre-voltage stress

➤ DPT results will be affected.

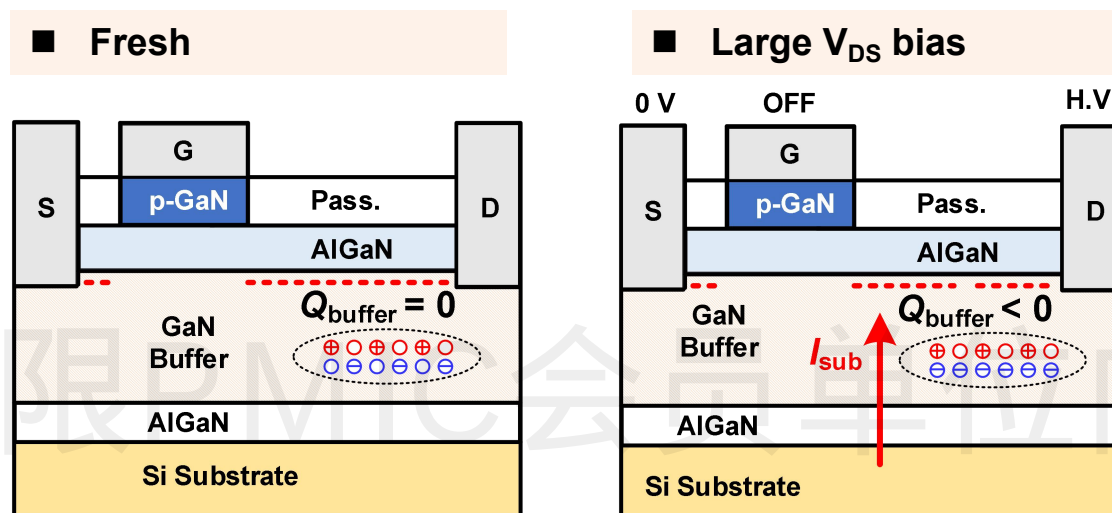
■ Connect 1 to 2 (HS).  
Pre-voltage stress =  $V_{in}$



■ Connect 1 to 3 (SS).  
Pre-voltage stress =  $\frac{1}{2} V_{in}$

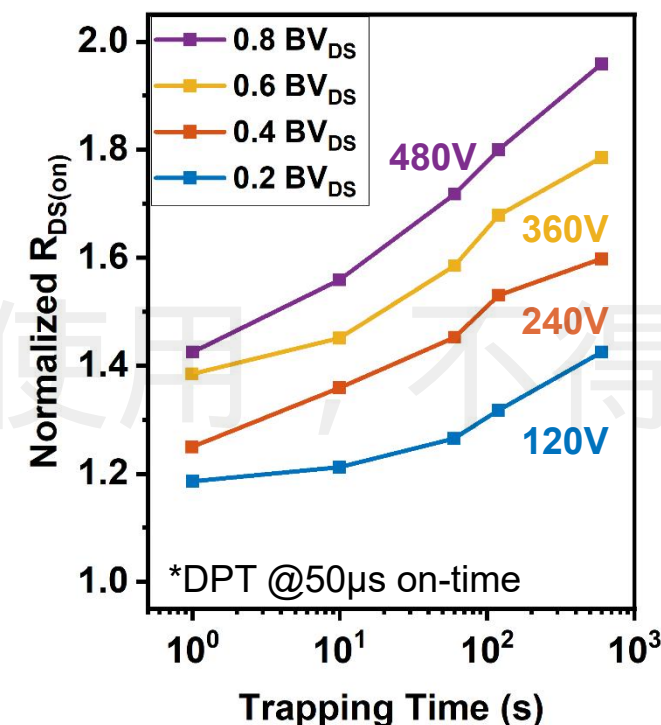


## ➤ OFF-state Trapping [8]



- ❑ Lead to 2DEG depletion.
- ❑ Trapped electrons **increase with  $V_{DS}$  bias.**

## ➤ Dynamic $R_{DS(on)}$ vs. $V_{DS}$ bias [9]



## ➤ $V_{DS}$ bias seriously influence the dynamic $R_{DS(on)}$

[8] S. Yang, C. Zhou, S. Han, K. Sheng, and K. J. Chen, "Buffer trapping-induced RON degradation in GaN-on-Si power transistors: Role of electron injection from Si substrate,"

[9] G. Zulauf, M. Guacci, and J. W. Kolar, "Dynamic on-Resistance in GaN-on-Si HEMTs: Origins, Dependencies, and Future Characterization Frameworks,"